Microlithography Committee Meeting

SEMICON West Meetings 2009
San Francisco Marriott
Tuesday, July 14, 2009
3:00 PM to 5:00 PM

Agenda

1.0 Call to Order
- 1.1 Introduction
- 1.2 Anti-Trust Reminder
- 1.3 Intellectual Property Reminder
- 1.4 International Meeting Guidelines
- 1.5 Agenda Review

2.0 Review and Approval of Spring Meeting Minutes

3.0 Staff & Liaison Reports
- 3.1 SEMI Staff Report
- 3.2 SEMI Japan
- 3.3 SEMI Europe

4.0 Ballot Review
- 4.1 Doc. 4584A, Revision to P40, Specification for Mounting Requirements and Alignment Reference Locations for Extreme Ultraviolet Lithography Masks
- 4.2 Doc. 4584, Revision to P37-1102, Specification for Extreme Ultraviolet Lithography Mask Substrates With Title Change To: Specification For Extreme Ultraviolet Lithography Substrates And Blanks

5.0 Task Force Reports
- 5.1 Data Path
- 5.2 EUV Mask
- 5.3 EUV Reticle Fiducial Mark
- 5.4 Mask Orders (P10)
- 5.5 Overlay Metrology Specifications
- 5.6 Terminology of Metrology
- 5.7 Scatterometry

6.0 SNARFs & TFOFs

7.0 Old Business
- 7.1 Previous Action Items
  - 7.1.1 Wes Erck and Susan Turner to continue working the Liquid Chemicals Committee for Microlithography photoresist standards due for 5-Year Review

8.0 New Business
- 8.1 Next Meeting Fall 2009 – TBA
- 8.2 5-Year Review
- 8.3 Ballot Submission Dates
  - 8.3.1 Cycle 5 submission date: July 27, 2009
  - 8.3.2 Cycle 6 submission date: August 31, 2009

9.0 Review
- 9.1 Action item review

10.0 Adjournment